

Appn No. 09/693,079
Amdt. Dated October 22, 2003
Reply to Office action of December 30, 2002

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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1 – 4 (cancelled)

5. (currently amended) An expansive element in a thermoelastic design that is made from any functionally suitable a material or combinations of materials selected from a group including: silicides and carbides of titanium the material or combination of materials being selected to have one or more of the following properties:

- (a) a resistivity between 0.1 $\mu\Omega$ m and 10.0 $\mu\Omega$ m;
- (b) chemically inert in air;
- (c) chemically inert in the chosen ink; and
- (d) depositable by CVD, sputtering or other thin film deposition technique.

6. (deleted)

7. (currently amended) An expansive element in a thermoelastic design that is made from any functionally suitable a material or combinations of materials selected from a group including: borides, silicides, carbides and nitrides of tantalum, molybdenum, niobium, chromium, tungsten, vanadium, and zirconium, and having one or more of the following properties:

- (e) a resistivity between 0.1 $\mu\Omega$ m and 10.0 $\mu\Omega$ m;
- (f) chemically inert in air;
- (g) chemically inert in the chosen ink; and
- (h) depositable by CVD, sputtering or other thin film deposition technique.

8. (deleted)

9. (currently amended) An expansive element in a thermoelastic design that is made from any functionally suitable an alloy material or combinations of alloy materials selected from the group including: borides, silicides, carbides and nitrides of titanium, tantalum, molybdenum, niobium, chromium, tungsten, vanadium, and zirconium, and having one or more of the following properties:

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- (i) a resistivity between 0.1 $\mu\Omega$ m and 10.0 $\mu\Omega$ m;
- (j) chemically inert in air;
- (k) chemically inert in the chosen ink; and
- (l) depositable by CVD, sputtering or other thin film deposition technique.

10. (deleted)